

1 WHAT IS CLAIMED IS:

 1. An electron-emitting device comprising
a pair of oppositely disposed electrodes and an
electroconductive film arranged between the electrodes
5 and including a high resistance region, characterized
in that the high resistance region has a deposit
containing carbon as a principal ingredient.

 2. An electron-emitting device according to
10 claim 1, wherein said deposit containing carbon as a
principal ingredient is also present in the vicinity
of said high resistance region.

 3. An electron-emitting device according to
15 claim 2, wherein said deposit containing carbon as a
principal ingredient is present on said electroconductive
film from part of said high resistance region.

 4. An electron-emitting device according to
20 claim 3, wherein said deposit containing carbon as a
principal ingredient is present particularly on one of
said electrodes from said high resistance region.

 5. An electron-emitting device according to
25 claim 4, wherein said deposit containing carbon as a
principal ingredient is present particularly on part
of the electroconductive film close to the higher

1 potential one of said electrodes from said high
resistance region.

6. An electron-emitting device according to
5 claim 1, wherein said electroconductive film is made
of electroconductive fine particles.

7. An electron-emitting device according to
claim 6, wherein said electroconductive fine particles
10 are made of metal or an oxide of metal.

8. An electron-emitting device according to
claim 6, wherein at least part of said electroconductive
fine particles are coated with said deposit.
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9. An electron-emitting device according to
claim 1, wherein said high resistance region contains
electroconductive fine particles.

10. An electron-emitting device according to
20 claim 9, wherein at least part of said electroconductive
fine particles are coated with said deposit.

11. An electron-emitting device according to
25 claim 1, wherein at least part of said electrodes are
coated with said deposit containing carbon as a
principal ingredient.

1 12. An electron-emitting device according
to claim 1, wherein said deposit containing carbon as
a principal ingredient is principally made of graphite,
amorphous carbon or a mixture thereof.

5 13. An electron-emitting device according to
claim 1, wherein the electron emission current of the
device has a monotonically increasing characteristic
relative to the voltage applied to said electrodes.

10 14. An electron source comprising an electron-
emitting device for emitting electrons according to
input signals, characterized in that said electron-
emitting device is a device according to one of claims
15 1 through 13.

 15. An electron source according to claim 14,
wherein it comprises a plurality of said electron-
emitting devices arranged in a plurality of rows, each
20 of said electron-emitting devices being connected to
wirings at opposite ends, and a modulation means for
modulating electron beams emitted from said electron-
emitting devices.

25 16. An electron source according to claim 14,
wherein it comprises a plurality of said electron-
emitting devices arranged in rows and respectively

1 connected to m X-directional wirings and n Y-directional
wirings that are mutually electrically insulated.

17. An image-forming apparatus comprising an
5 electron source and an image-forming member for forming
images according to input signals characterized in that
said electron source comprises an electron-emitting
device according to one of claims 1 through 13.

10 18. An image-forming apparatus according to
claim 17, wherein said electron source comprises a
plurality of said electron-emitting devices arranged
in a plurality of rows, each of said electron-
emitting devices being connected to wirings at opposite
15 ends, and a modulation means for modulating electron
beams emitted from said electron-emitting devices.

19. An image-forming apparatus according to
claim 17, wherein said electron source comprises a
20 plurality of said electron-emitting devices arranged
in rows and respectively connected to m X-directional
wirings and n Y-directional wirings that are mutually
electrically insulated.

25 20. An image-forming apparatus according to
claim 17, wherein the emission current and the device
current of said electron source have a monotonically

1 increasing characteristic relative to the voltage
applied to said devices.

5 21. An image-forming apparatus according to
claim 17, wherein the inside of said image-forming
apparatus is maintained to a degree of vacuum that
does not allow any additional deposition to be made
to said deposit containing carbon as a principal
ingredient.

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22. A method of manufacturing an electron-
emitting device comprising a pair of oppositely disposed
electrodes and an electroconductive film arranged
between the electrodes, characterized in that it
15 comprises a device activation process.

23. A method of manufacturing an electron-
emitting device according to claim 22, wherein said
activation process is a process for depositing a deposit
20 containing carbon as a principal ingredient on said
electroconductive film.

24. A method of manufacturing an electron-
emitting device according to claim 23, wherein said
25 activation process comprises a step of applying a
voltage to the electroconductive film arranged
between the electrodes in vacuum.

1 25. A method of manufacturing an electron-emitting device according to claim 24, wherein said voltage is applied in the form of pulse.

5 26. A method of manufacturing an electron-emitting device according to claim 25, wherein said voltage is above a voltage-controlled-negative-resistance level.

10 27. A method of manufacturing an electron-emitting device according to claim 26, wherein said voltage is a drive voltage for driving the electron-emitting devices.

15 28. A method of manufacturing an electron-emitting device according to claim 23, wherein said activation process comprises a step of applying a voltage to the electroconductive film arranged between the electrodes in an atmosphere containing an introduced
20 carbon compound.

 29. A method of manufacturing an electron-emitting device according to claim 28, wherein said voltage is applied in the form of pulse.

25 30. A method of manufacturing an electron-emitting device according to claim 29, wherein said

1 voltage is above a voltage-controlled-negative-
resistance level.

5 31. A method of manufacturing an electron-
emitting device according to claim 30, wherein said
voltage is a drive voltage for driving the electron-
emitting devices.

10 32. A method of manufacturing an electron-
emitting device according to claim 28, wherein said
carbon compound is an organic gas.

15 33. Method of manufacturing an electron-
emitting device according to claim 32, wherein said
organic gas has a vapor pressure of not higher than
5,000hPa at the temperature and in the atmosphere of
the activation process.

20 34. A method of manufacturing an electron-
emitting device according to claim 33, wherein said
organic gas has a vapor pressure of not higher than
5,000hPa at 20°C.

25 35. A method of manufacturing an electron-
emitting device according to claim 32, wherein said
organic gas has a vapor pressure between 0.2hPa and
5,000hPa at the temperature and in the atmosphere of

1 the activation process.

36. A method of manufacturing an electron-
emitting device according to claim 35, wherein said
5 organic gas has a vapor pressure between 0.2hPa and
5,000hPa at 20°C.

37. A method of manufacturing an electron-
emitting device according to claim 22, wherein it
10 further comprises a forming process.

38. A method of manufacturing an electron-
emitting device according to claim 37, wherein said
forming process is a step of forming a high resistance
15 region in the electronconductive film arranged between
the electrodes.

39. A method of manufacturing an electron-
emitting device according to claim 22, wherein said
20 activation process is carried out after said forming
process.

40. An electron source comprising an electron-
emitting device for emitting electrons according to
25 input signals, characterized in that said electron-
emitting device is manufactured by a method according
to one of claims 22 through 39.

1 41. An electron source according to claim 40,
wherein it comprises a plurality of said electron-
emitting devices arranged in a plurality of rows, each
of said electron-emitting devices being connected to
5 wirings at opposite ends, and a modulation means for
modulating electron beams emitted from said electron-
emitting devices.

 42. An electron source according to claim 40,
10 wherein it comprises a plurality of said electron-
emitting devices arranged in rows and respectively
connected to m X-directional wirings and n Y-
directional wirings that are mutually electrically
insulated.

15 43. An image-forming apparatus comprising an
electron source and an image-forming member for
forming images according to input signals characterized
in that said electron source comprises an electron-
20 emitting device manufactured by a method according to
one of claims 22 through 39.

 44. An image-forming apparatus according to
claim 43, wherein said electron source comprises a
25 plurality of said electron-emitting devices arranged
in a plurality of rows, each of said electron-emitting
devices being connected to wirings at opposite ends,

1 and a modulation means for modulating electron beams
emitted from said electron-emitting devices.

5 45. An image-forming apparatus according to
claim 43, wherein said electron source comprises a
plurality of said electron-emitting devices arranged
in rows and respectively connected to m X-directional
wirings and n Y-directional wirings that are mutually
electrically insulated.

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46. An image-forming apparatus according to
claim 43, wherein the emission current and the device
current of said electron source have a monotonically
increasing characteristic relative to the voltage
15 applied to said devices.

47. An image-forming apparatus according to
claim 43, wherein the inside of said image-forming
apparatus is maintained to a degree of vacuum that
20 does not allow any additional deposition to be made
to said deposit containing carbon as a principal
ingredient.

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